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## PATENT ABSTRACTS OF JAPAN

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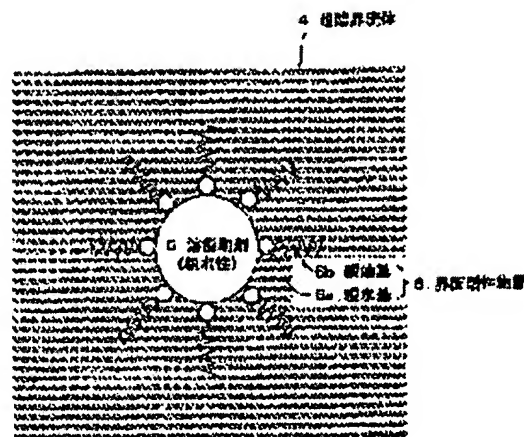
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## (54) SURFACE TREATMENT METHOD

## (57)Abstract:

PROBLEM TO BE SOLVED: To provide a surface treatment method which can surely eliminate residue by only treatment using supercritical fluid.

SOLUTION: In the surface treatment method wherein a surface on which a structure is formed is treated by the supercritical fluid 4, ammonium hydroxide, alkanolamine, amine fluoride, hydrofluoric acid, etc., are added as solubilizer 5 to the supercritical fluid 4. A surfactant 6 may be added to the supercritical fluid 4 together with a solubilizer 5. A polar solvent may be used as the surfactant 6.



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